

REMARKS

Claims 1-5, 7-9 and 11-17 are pending.

Response to Claim Rejections Under § 103

A. Claims 1-5 and 15-17 have been rejected under 35 U.S.C. §103(a) as allegedly being unpatentable over JP 2002-023356 to Ishida in view of U.S. Patent No. 4,687,707 to Matsuo et al; and

B. Claims 1-5 and 15-17 have been rejected under 35 U.S.C. §103(a) as allegedly being unpatentable over Ishida in view of EP 1041652 to Katz et al. and Matsuo.

Applicants respectfully traverse.

(i) At page 9, fourth full paragraph of the Office Action, the Examiner addresses Applicants' argument that the Examiner's position that 'heptadecafluoro tetrahydro decyltrichlorosilane is an equivalent for urethane containing linkages," is in error.

The Examiner misunderstands Applicants' arguments set forth on page 13 of the Amendment filed May 3, 2010.

Applicants did not argue that the Examiner's position that "heptadecafluoro tetrahydro decyltrichlorosilane is an equivalent for urethane containing linkages" is in error. Rather, Applicants argued, and maintain, that heptadecafluoro tetrahydro decyltrichlorosilane is not an equivalent for urethane-containing linkages that read on option "(d)". More particularly, heptadecafluoro tetrahydro decyltrichlorosilane, i.e., $\text{CF}_3(\text{CF}_2)_7\text{C}_2\text{H}_4\text{SiCl}_3$, does not have an Rf group which is a perfluoroalkyl group having 5 or less carbon atoms. $\text{CF}_3(\text{CF}_2)_7\text{C}_2\text{H}_4\text{SiCl}_3$ has a perfluoroalkyl group having 8 carbon atoms. See, col. 4, lines 45-47.

In contrast, according to the presently claimed invention, the number of carbons in the perfluoroalkyl group (or fluoroalkyl group) is limited to 5 or less. Thus, the heptadecafluoro tetrahydro decyltrichlorosilane of Matsuo fails to read on any of the presently claimed compounds (a)-(f), as recited on present Claim 1. Moreover, not only does Matsuo fail to disclose or suggest that R_f should have 5 or less carbon atoms, Matsuo does not disclose or suggest the presently claimed compounds (d)-(f), and more particularly, presently claimed compound (d).

(ii) At page 10, third paragraph of the Office Action, the Examiner asserts that Applicants “admit that Matsuo teaches compounds containing perfluoroalkyl groups having 5 or less carbon atoms,” and as such, the Examiner takes the position that he has provided a proper *prima facie* case to use these compounds.

The Examiner, again, misunderstands Applicants’ argument.

As an initial matter, Applicants note that the Examiner appears to be making an argument for anticipation. Even so, Applicants did not “admit” that Matsuo teaches compounds containing perfluoroalkyl groups having 5 or less carbon atoms, as the Examiner asserts. Rather, Applicants argued, and maintain, that while Matsuo may disclose one silane having a perfluoroalkyl group having 5 or less carbon atoms, Matsuo does not disclose or suggest a fluorine compound of the formula R_f-A-Z-A’-SiX₃ wherein R_f represents a perfluoroalkyl group having 5 or less carbon atoms with sufficient specificity to arrive at the presently claimed component (d).

(iii) Regarding the motivation of one skilled in the art to use the compounds of Matsuo in the device of Ishida, the Examiner has failed to identify any reason in the cited references that

would have prompted a person of ordinary skill in the relevant field to combine the elements at issue in the way that the present invention does, and that one of ordinary skill in the art would not have possessed a reasonable expectation of success in making such a combination (a fundamental requirement of KSR).

Matsuo is directed to a low reflectance transparent material having antisoiling properties, which comprises a transparent substrate and a multi-layer coating formed thereon (Abstract). There is no discussion in Matsuo of forming an alternating line pattern of self-organization organic thin films, and there is no discussion in Matsuo of using a coating of Matsuo for forming a fine line pattern structure which is the subject matter of Ishida. In this regard, the Examiner has failed to set forth a reason that would have prompted a person of ordinary skill in the device/(photo)lithography field to employ a silane compound of Matsuo for use in coating an optical part having no alternating line pattern. The Examiner merely relies on conclusory statements to support his position, which is improper under KSR.

In addition, it is difficult to understand how one of ordinary skill in Ishida's field of art would have at least a reasonable expectation of success in making such a substitution.

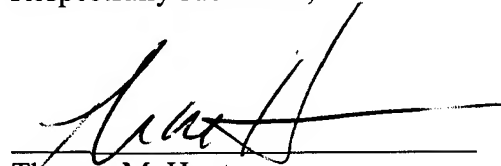
Katz fails to make up for the deficiencies noted above.

Thus, Ishida, Katz and Matsuo fail to render obvious the present claims. Accordingly, withdrawal of the rejections and rejoinder of method Claims 7 and 8 are respectfully requested.

In view of the above, reconsideration and allowance of this application are now believed to be in order, and such actions are hereby solicited. If any points remain in issue which the Examiner feels may be best resolved through a personal or telephone interview, the Examiner is kindly requested to contact the undersigned at the telephone number listed below.

The USPTO is directed and authorized to charge all required fees, except for the Issue Fee and the Publication Fee, to Deposit Account No. 19-4880. Please also credit any overpayments to said Deposit Account.

Respectfully submitted,



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